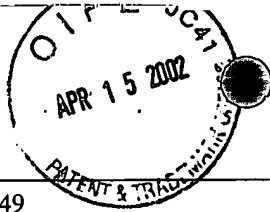
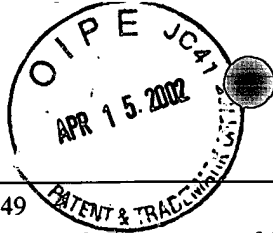


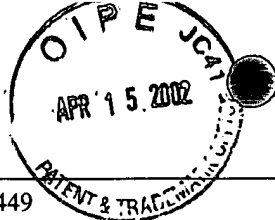
Form PTO 1449 (Rev. 2-32) U.S. Department of Commerce Patent and Trademark Office				Atty. Docket No. LMPY-9220		Serial No.: 09/771,366	
Information Disclosure Statement by Applicant				Applicant: Dirk Basting, et al.			
(Use several sheets if necessary)				Filed: January 15, 2001 Group: 2881 2828			
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Init.		Document No.	Date	Name	Class	Subclass	Filing Date
<i>JS</i>		3,471,800	10/07/69	Congleton, et al.	331	94.5	12/17/64
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Examiner <i>JS</i> <i>Pepper</i> <i>Baum</i>					Date Considered <i>9/4/2003</i>		
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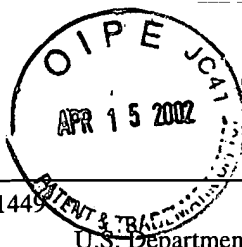
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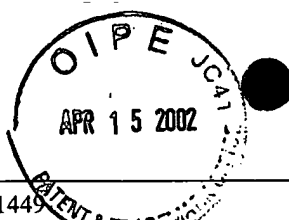
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83		5,978,394	11/02/99	Newman, et al.	372	32	10/02/98
Examiner <i>JERRY ZAHN</i>					Date Considered <i>9/4/2003</i>		
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J3		5,978,406	11/02/99	Rokni, et al.	372	58	01/30/98	
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J3		6,327,290	12/04/01	Govorkov, et al.	372	61	06/14/00	
		6,345,065	02/05/02	Kleinschmidt, et al.	372	57	05/24/99	
Foreign Documents								
Translation								
Init.		Document No.	Date	Country	Class	Subclass	Yes	No
J3		44-8147	1969	Japan	100	D0		X
		60-205420	10/17/85	Japan	G02B	27/00	Abstract	
		8-274399	11/18/86	Japan	H04S	3/104	X	
		61-139950	06/1986	Japan				
		62-160783	07/16/87	Japan	H01S	3/115	X	
Examiner JPP/NOT ZAMN					Date Considered 9/4/03			
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Init.		Document No.	Date	Country	Class	Subclass	Yes	No
13		10-209533	1998	Japan	H01S	3/08		X
		63-45875	1988	Japan	H01S	3/08		X
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		JP 3-139893	06/14/91	Japan	H01S	3/1055	Abstract	
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		WO 98/57213	12/17/98	PCT	G02B	27/00		X
		WO 98/59364	12/30/98	PCT	H01L	21/027		X
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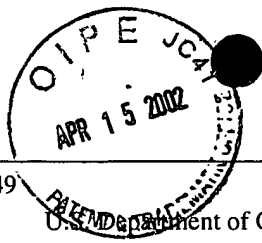


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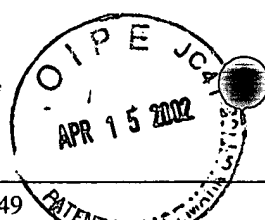
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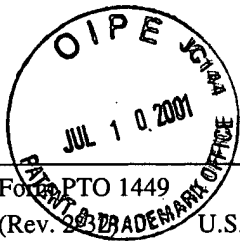


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Init.		Document No.	Date	Name	Class	Subclass	Filing Date	
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Foreign Documents								
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